

## ABSTRACT OF THE DISCLOSURE

5           The present invention is an apparatus for storing and delivering a low vapor  
pressure process chemical to a process tool for semiconductor fabrication, comprising:  
a) a bulk container for storing the process chemical; b) a process container for delivering  
the process chemical to the process tool; c) a first manifold for delivering process  
chemical from the bulk container to the process container; d) a solvent container  
10   containing a quantity of solvent, and; e) a second manifold for delivering the process  
chemical from the process container to a process tool. A process for using the  
apparatus is also contemplated.